

Study of the Photo thermal Response of a Mono facial Solar Cell in Dynamic Regime under a Multi-spectral Illumination and under magnetic field

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Abstract: In this article, we present the study of the photo thermal response of a monofacial silicon solar cell illuminate by a multispectral light for a constant modulated frequency and under magnetic field. after the resolution of the equation of continuity of the minority carriers of loads, we establish with the help of some justified approximations, the equations of heat in the presence of an optical source of heat and the new boundary conditions allowing to solve those. The density of minority carriers in excess, the amplitude of the variation of temperature and the heat flux density were studied and analyzed for different angular pulses and for different values of the magnetic field and rates of recombination at the junction. Representations of Nyquist and Bode plots of the thermal dynamic impedance resulted in an equivalent electrical circuit of the photocell.

Keywords: solar cell- frequency modulation- magnetic field - Capacitive effect ,inductive effect, photo thermal.

I. INTRODUCTION

We will make the study of a photovoltaic cell monofacial to silicon lit by a constant multispectral light in frequential dynamic mode and under the effect of a magnetic field. In this present article, we init ially will make a short description of the photovoltaic cell bifacial and then we will see the evolution of the coefficient of diffusion according to the intensity of the magnetic field, the density of minority carriers according to the depth and of the intensity of the magnetic field. We then will study the thermal behavior of the photovoltaic cell. We also will study the influence of the pulsation on these parameters.

THEORY

Photovoltaic response (minority carriers' density in excess):

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We consider solar silicon with a Back Surface Field(B.S.F) for the structure n+pp+ (LeQuangNam et al., 1992). Given that the contribution of the base to the Photocurrent is larger than that of the emitter (Barro et al., 2001; Lemrabet et al., 2008), the univariate analysis will only be developed in the base region. In addition, we consider the hypothesis of Quasi-Neutral Base (Q.N.B) neglecting the crystal field with in the solar cell. In Fig.1, we represent a schematic sketch of a multicrystalline silicon solar cell with a Back Field (BSF) typically n+-p-p+ in a magnetic field.

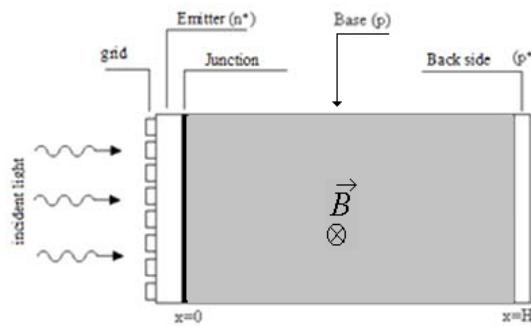


Fig.1: A monofacial solar cell under a multispectral illumination from a modulated frequency and under magnetic field

When the photovoltaic cell receives solar radiation, the transformation is done in three stages:

- ✓ absorption of the photons by material
- ✓ creation of pair electron-positron pair which will be separated by an intense electric field on the level from the zone of space charge
- ✓ collection of the particles in an external circuit

The solar cell is subjected to a constant multispectral illumination from a source of modulated frequency and under magnetic field effect and the phenomena of generation, diffusion and recombination of photogenerated carriers in the base are reconsidered. These phenomena are governed by the continuity equation:

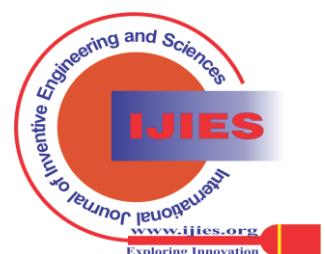
$$D(\omega, B) \frac{\partial^2 \delta(x, t, \omega, B)}{\partial x^2} - \frac{\delta(x, t, \omega, B)}{\tau} + G(x, t) = \frac{\partial \delta(x, t, \omega, B)}{\partial t}$$

(1)

$\delta(x, t)$

the density of the minority carriers in the base which can be written in the form:

$$\delta(x, t) = \delta(x) e^{i\omega t} \quad (2)$$



$g(x, t)$ the optical rate of generation given by the expression:

$$G(x, t) = g(x) \cdot e^{i\omega t} \quad (3)$$

$\delta(x)$ and $g(x)$

represent respectively the spatial components of the carrier density y and the rate of generation.

And the term $e^{i\omega t}$

represents the time component for the carrier density and the rate of optical generation.

Comparing the above equations for which incident optical beam and the density of photo generated carriers, the Eq.(1) is simplified and becomes as follows:

$$\frac{\partial^2 \delta(x)}{\partial x^2} - \frac{\delta(x)}{L(\omega, B)^2} + \frac{g(x)}{D(\omega, B)} = 0 \quad (4)$$

The coefficient D which describes the diffusive character of the minority carriers in material, is function of the frequency of modulation and the intensity of the magnetic field and is given by the expression:

$$D(\omega, B) := D_0 \frac{\left[1 + \tau^2 (\alpha(B)^2 + \omega^2) + i\omega\tau \cdot \left[\tau^2 (\alpha(B)^2 - \omega^2) - 1 \right] \right]}{4\tau^2 \cdot \omega^2 + \left[1 + \tau^2 (\alpha(B)^2 - \omega^2) \right]^2} \quad (5)$$

$$\text{And } \frac{1}{L(\omega)^2} = \frac{1}{Ln^2} \times (i\omega\tau + 1) \quad (6)$$

Where $L(\omega, B)$ is the complex scattering length. The spatial component $g(x)$ is a rate of optical generation of electron hole pairs for multispectral illumination from a constant modulated frequency and it reflects the entire spectrum of useful radiation incident on the solar cell, it is thus given by the following expression:

$$g_\gamma(x) = \sum_{\lambda_0}^{\lambda_g} \alpha(\lambda) \phi(\lambda) (1 - R(\lambda)) (\xi e^{-\alpha(\lambda)x} + \chi e^{-\alpha(\lambda)(H-x)}) \quad (7)$$

Where $\alpha(\lambda)$ and $R(\lambda)$ represent respectively the absorption coefficient and the reflection coefficient of the material for a given wavelength;

$\phi(\lambda)$ is the flux of incident photons.

λ_g : Wavelength of cut off the semiconductor estimated at $1,12\mu\text{m}$
 λ_0 : The minimal wavelength of the source luminous is equal to $0,3\mu\text{m}$ [36];
 H : the solar cell base thickness.

τ is the average lifetime of the minority carriers of load.

The density of minority charge carriers in excess (electrons) is given by the expression:

$$\delta(x) = A(\omega) \cosh\left(\frac{x}{L(\omega)}\right) + B(\omega) \sinh\left(\frac{x}{L(\omega)}\right) + \sum_{\lambda_0}^{\lambda_g} k(\omega, \lambda) (\xi e^{-\alpha(\lambda)x} + \chi e^{-\alpha(\lambda)(H-x)}) \quad (8)$$

With

$$k(\omega, \lambda) = \frac{\alpha(\lambda) \phi(\lambda) (1 - R(\lambda)) L(\omega, B)^2}{D(\omega, B)^2 (1 - L(\omega, B)^2 \alpha(\lambda)^2)} \quad (9)$$

Using the boundary conditions (Dien et al., 2007) presented in Eq.(10) and (11), the coefficients $A(\omega, B)$ and $B(\omega, B)$ are determined.

At the emitter-base junction ($x=0$) of the solar cell:

$$\frac{\partial \delta(x)}{\partial x} \Big|_{x=0} = Sf \frac{\delta(0)}{D(\omega)} \quad (10)$$

At the rear side of the cell base ($x=H$):

$$\frac{\partial \delta(x)}{\partial x} \Big|_{x=H} = -Sb \frac{\delta(H)}{D(\omega)} \quad (11)$$

S_f and S_b are respectively the recombination velocity at the junction and at the rear surface of the base.

The recombination velocity S_f is imposed by a varying impedance of an external load and by the interface states at the junction:

$$S_f = S_f 0 + S_f m \quad (12)$$

Indeed, S_f is the sum of two contributions:

$S_f 0$ is the intrinsic recombination velocity (depending only on the intrinsic parameters of the solar cell and is induced by the shunt resistor),

$S_f m$ reflects the leakage current induced by the external load and for the operating point of the solar cell (Diallo et al., 2008; Dème et al., 2009).

Photothermal response(excess temperature across the solar cell):

When a solar cell is subjected to a multispectral optical excitation from a constant modulated frequency and under magnetic field, the minority charge carrier (electrons) is generated in the base. The movement of such carriers (diffusion and migration) in the solar cell generates a heat flux and an excess temperature different from the equilibrium temperature of the material. For a small temperature change compared to the initial temperature T_0 , the heat flux in the solar cell can be described by this equation:

$$a \cdot \frac{\partial^2 \Delta T(x, t, B)}{\partial x^2} + \frac{G_H(x, t, B)}{\rho \cdot c} = \frac{\partial \Delta T(x, t, B)}{\partial t} \quad (13)$$

a is the thermal diffusivity of material, ρ the density and C_i specific heat.

The terms $\Delta T(x, t, B)$ and $G_H(x, t, B)$ which represent the change in temperature from the initial temperature T_0 and the rate of heat generation with time written:

$$\Delta T(x, t, B) = \Delta T(x, B) \cdot e^{i\omega t} \quad (14)$$

$$G_H(x, t, B) = G_H(x, B)^\pm e^{i\omega t} \quad (15)$$

$\Delta T(x, B)$ and $G_H(x, B)$ are the spatial components of the temperature and rate of heat generation.

The term

represents the time component of the temperature and rate of heat generation.

This time component has the same pulse as the incident optical beam at each time.

Equation (13) can be rewritten:

$$\frac{\partial^2 \Delta T(x, B)}{\partial x^2} - \sigma(\omega)^2 \Delta T(x, B) + \frac{G_H(x, B)}{k} = 0 \quad (16)$$

With

$k = a \cdot \rho \cdot c$ is the thermal conductivity of the material

$$\sigma(\omega) = \left(\frac{i \cdot \omega}{a} \right)^{1/2}$$

is the complex thermal diffusion coefficient of the material.

The spatial component $G_H(x, B)$ of the rate of heat generation is given by the equation:

$$G_H(x, B) = \sum_{\lambda_0}^{\lambda_g} \alpha(\lambda) \phi(\lambda) [1 - R(\lambda)] \Delta E(\lambda) e^{-\alpha(\lambda)x} + \frac{E_g \cdot \delta(x)}{k \tau}$$

First zone: The gradient of the density of the carriers is positive; this is translated by a passage of the minority carriers through the junction

(17)

With E_g is the energy gap of the semiconductor material

$$\Delta E = h\nu - E_g$$

is the energy thermalization resulting from the relaxation of optically excited carriers was due to absorption of photons of energy greater than the energy gap E_g .

The heat equation (13) can be expressed as:

$$\frac{d^2 \Delta T(x, B)}{dx^2} - \sigma(\omega, B)^2 \Delta T(x, B) = \frac{E_g}{k \tau} \left\{ A_1(\omega, B) \cdot ch\left(\frac{x}{L(\omega)}\right) + A_2(\omega, B) \cdot sh\left(\frac{x}{L(\omega)}\right) \right. \\ \left. - \sum_{\lambda_0}^{\lambda_g} \frac{\alpha(\lambda) \phi(\lambda) [1 - R(\lambda)]}{k} \left\{ \Delta E + \frac{E_g \cdot L(\omega, B)^2}{D(\omega, B) \cdot \tau [1 - \alpha(\lambda)^2 \cdot L(\omega, B)^2]} \right\} e^{-\alpha(\lambda)x} \right\}$$

(18)

The excess temperature of the movement of minority carriers in the material, solution of the above equation is of the form:

$$\Delta T(x, \omega, B, m) = C_1(\omega, B, m) \cdot ch(\sigma x) + C_2(\omega, B, m) \cdot sh(\sigma x) \\ + \frac{E_g}{k \cdot \tau (\sigma(\omega)^2 - L(\omega, B)^2)} \left\{ A_1(\omega, B, m) \cdot ch\left(\frac{x}{L(\omega, B)}\right) + A_2(\omega, B, m) \cdot sh\left(\frac{x}{L(\omega, B)}\right) \right\} \\ + \sum_{\lambda_0}^{\lambda_g} \frac{\alpha(\lambda) \phi(\lambda) [1 - R(\lambda)]}{k [\sigma(\omega)^2 - \alpha(\lambda)^2]} \left\{ \Delta E + \frac{E_g \cdot L(\omega, B)^2}{D(\omega, B) \cdot \tau [1 - \alpha(\lambda)^2 \cdot L(\omega, B)^2]} \right\} e^{-\alpha(\lambda)x}$$

(19)

The constants $C_1(\omega, B, m)$ and $C_2(\omega, B, m)$ are determined by the following boundary conditions:

At the emitter-base junction ($x=0$)

$$\frac{\partial \Delta T(x, \omega, B)}{\partial x} \Big|_{x=0} = S_f \frac{E_g \delta(x=0, \omega, B)}{k} \quad (20)$$

At the rear of the base ($x=H$):

$$\frac{\partial \Delta T(x, \omega, B)}{\partial x} \Big|_{x=H} = -S_b \frac{E_g \delta(\omega, x=H, B)}{k} \quad (21)$$

II. RESULTS

Photovoltaic response (profile of the density of minority carriers):

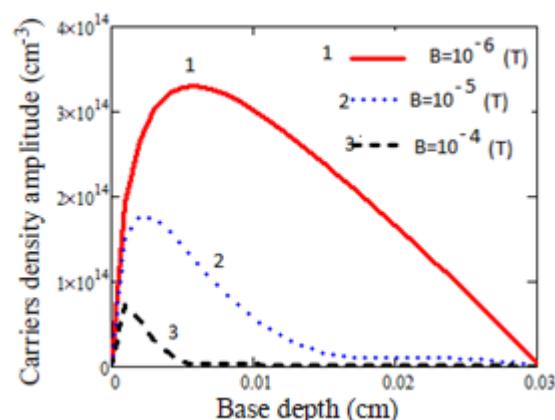


Fig. 2 Minority carrier density versus the base depth for different values of the magnetic field.

$$H=0.03 \mu m; D=26 cm^2/s$$

When the photovoltaic cell is subjected to an illumination, the density of the minority carriers increases until reaching a maximum value from which it starts to decrease in depth. We distinguish three zones:

First zone: The gradient of the density of the carriers is positive; this is translated by a passage of the minority carriers through the junction

Second zone: the gradient of the density of the carriers is null; no carriers minority cross the junction: it there is storage

Third zone: the gradient of the density of the carriers is negative, which translates a reduction in crossed minority carriers through the junction involving a reduction in the photocurrent. In addition to the variations with depth x in the base, the density of minority carriers increases significantly with the magnetic field. Moreover, with the increase in the intensity of the magnetic field, the maximum of density moves toward the junction: that represents a storage of the carriers close to this junction. Thus the effect of the magnetic field on the photovoltaic cells supports the fast establishment of the open circuit.

Profile of the coefficient of diffusion of the minority carriers in excess

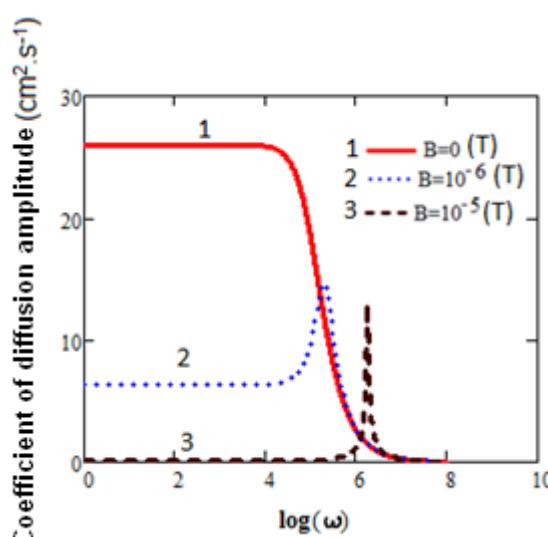


Fig. 3: Module of the coefficient of diffusion according to the logarithm of the pulsation for various values of the magnetic field $D=0.03 \mu m; H=0.03 \mu m$

In the absence of magnetic field applied to the photovoltaic cell, i.e. $B=0$, one distinguishes two zones on the curve obtained:

a first zone in the interval of pulsation $[0 \text{ rad/s}; 2 \cdot 10^4 \text{ rad/s}]$ in which the complex coefficient of diffusion remains practically constant (quasi-static mode)

second zone in the interval $[2 \cdot 10^4 \text{ rad/s}; 10^8 \text{ rad/s}]$ in which the complex coefficient of diffusion decreases clearly (strong frequency response of modulation)

The application of a magnetic field, makes leave a third zone where the coefficient of diffusion increases in a remarkable way until obtaining a peak: it is the phenomenon of resonance. This last is obtained when the frequency of modulation is equal to the frequency cyclotron (frequency of the electron orbit in the presence of a magnetic field) which, in its turn, is a linear function of the intensity of the magnetic field applied

Photothermic answer (profile of the temperature variation)

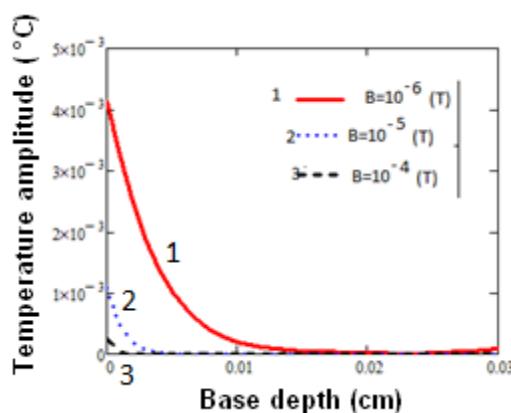


Fig.4:Moduleofthetemperaturevariationaccordingtodepth xinthebasefordifferentvaluefromthemagneticfield

The curves of figure 4 show that the temperature variation decreases with the depth of the base. It is maximum with the junction. In fact, close to the junction, the short wavelengths of the spectrum of solar radiation useful of silicon, absorptive involve an important generation of carriers with great energies (higher than the energy of the gap of silicon). These strong surplus energies of the carriers photogenerated close to the junction are lost by thermalization; what justifies the high value of the excess of temperature observed to the junction of the photovoltaic cell. In addition, in situation of short circuit, the junction is the place of convergence of carriers of load photogenerated inside the base of the photovoltaic cell. It results the presence from it from a high number of carriers in the junction and consequently a number of high shocks of emission of an important heat thus of an important excess of temperature. And just like the density of minority carriers of load, the temperature variation is strongly influenced by the intensity of the magnetic field close to the junction.

Profile of the temperature variation according to the speed of recombination to the junction

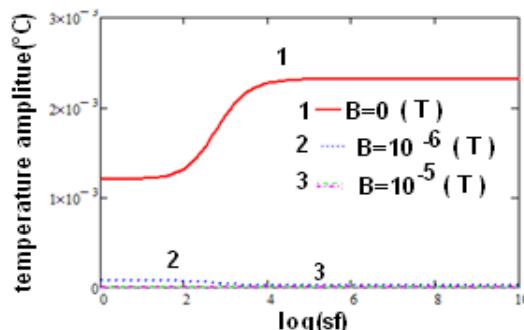


Fig.5:Moduleofthetemperaturevariationaccordingtothespeedofrecombinationtothejunctionforvariousvaluesofthemagneticfield.D=26cm2/sH=0.03μm,a=1cm2/s,k=1,54W/cm.°C

The curves of the figures show that the temperature with the junction of the photovoltaic cell is an increasing function the speed of recombination to the junction for a given pulsation. The temperature varies slightly with the low values the speed of recombination to the junction. Then, it increases gradually and reaches its maximum with the great values the speed of recombination to the junction i.e. in short-circuit. The application of the magnetic field decreases the amplitude of the temperature variation. Indeed, with the intensity of the magnetic field, the maximum of density moves toward the junction.

Thus with the great values the speed of recombination to the junction, the temperature variation decrease considerably.

Profile of the density flux

The expression of the density flux of heat is given by the following relation:

$$\phi(x, \omega, B, m) = -k \frac{\partial \Delta T(x, \omega, B, m)}{\partial x}$$

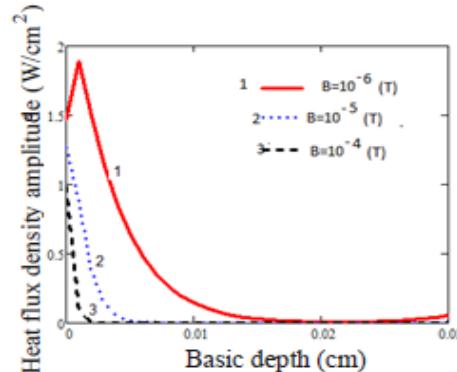


Fig.6:ModuleofthedensityofheatfluxasfunctionofdepthfordifferentvaluesofthemagneticfieldD=26cm2/s,H=0.03μm,a=1cm2/s,k=1,54W/cm.°C

The density flux of heat takes the same form as the temperature variation. Indeed, it is maximum with the junction of the photovoltaic cell and is a decreasing function of the depth of the base and angular pulsation of the signal.

Just like the density of the minority carriers, the density flux of heat increases significantly with the magnetic field because of the storage of the minority carriers of load close to the junction.

In addition, its amplitude decreases with the intensity of the magnetic field.

The behavior of the charge carriers described decreases at the time of the study of the variation in the temperature makes it possible to also explain the shape of the curves of density flux thermal.

Profile of the thermal impedance

The expression of the thermal impedance is given by the following relation

$$Z(x, \omega, B, m) = \frac{\Delta T(x, \omega, B, m)}{\phi(x, \omega, B, m)}$$

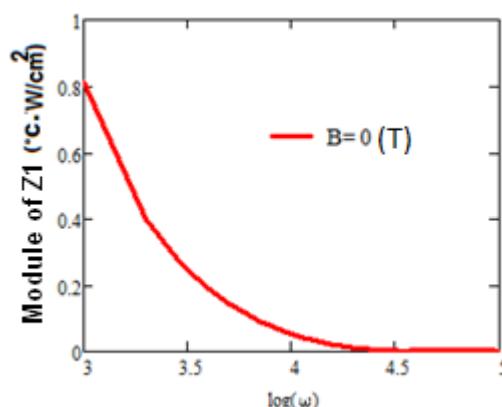


Fig.7:Moduleofthethermalimpedanceaccordingtothe logarithm of the pulsation for a null magnetic field

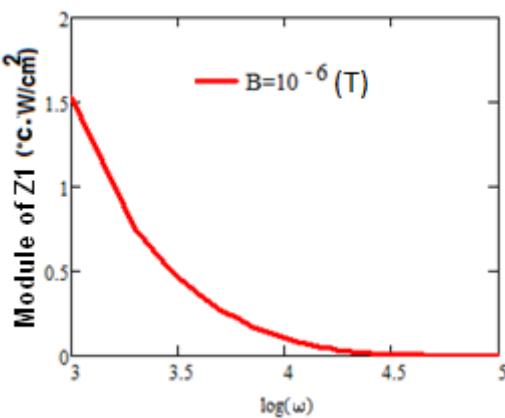


Fig.8: Module of the thermal impedance according to the logarithm of the pulsation in the presence of the magnetic field

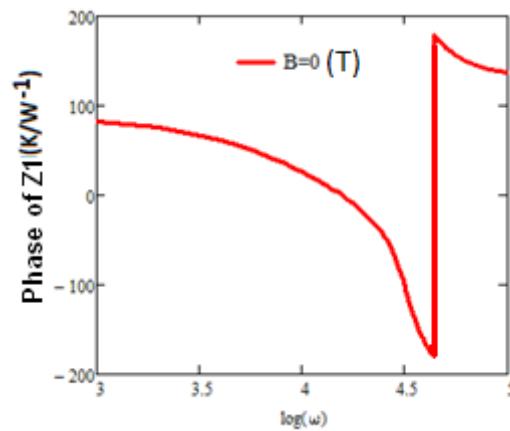


Fig.10: Phase of the thermal impedance according to the logarithm of the pulsation without magnetic field ($D = 26 \text{ cm}^2/\text{scm/s}$, $H = 0.03 \mu\text{m}$, $a = 1 \text{ cm}^2/\text{s}$, $k = 1,54 \text{ W/cm.}^{\circ}\text{C}$)

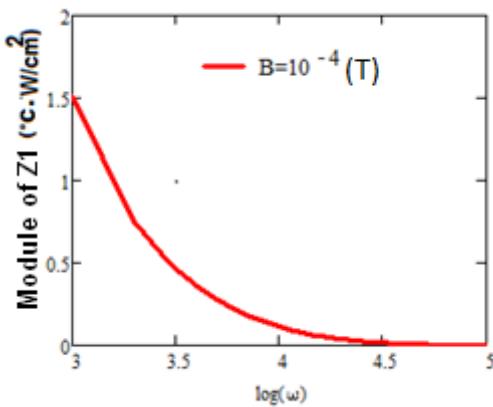


Fig.9: Module of the thermal impedance according to the logarithm of the pulsation in the presence of the magnetic field

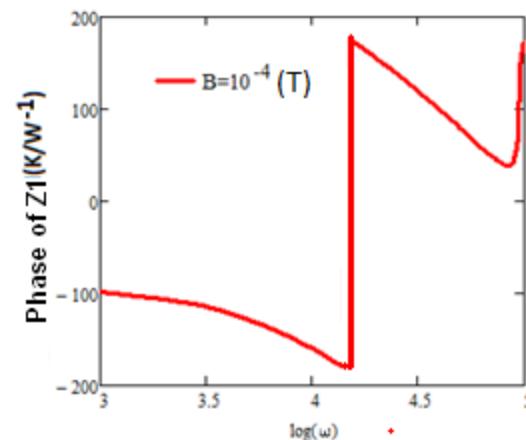


Fig.11: Phase of the thermal impedance according to the logarithm of the pulsation in the presence of a magnetic field ($D = 26 \text{ cm}^2/\text{scm/s}$, $H = 0.03 \mu\text{m}$, $a = 1 \text{ cm}^2/\text{s}$, $k = 1,54 \text{ W/cm.}^{\circ}\text{C}$)

In the absence of magnetic field (fig.10), when the pulsation is lower than 10^4 Hz, the phase of the thermal impedance is almost constant. For the pulsations ranging between 10^4 Hz and $10^{4.5}$ Hz, the phase increases and remains negative; in this field the capacitive effects overridethe inductive effects. For the frequencies higher than $10^{4.5}$ Hz, the phase increases and remains always negative; in this field the inductive effects overridethe capacitive effects.

The application of the magnetic field (fig.11), watch that: For the beaches of the pulsation going of 10^3 Hz with $10^{4.2}$ Hz, the capacitive effects overridethe inductive effects; When the pulsation is equal to $10^{4.2}$ Hz, the phase increases quickly, in this case the inductive effects overridethe capacitive effects. For the values of the pulsation ranging between $10^{4.2}$ Hz and 10^5 Hz, the phase decrease and remains positive, in this field the capacitive effects overridethe inductive effects. And beyond 10^5 Hz, the phase increases and remains always positive, infact the inductive effects overridethe capacitive effects. Thus one can note that the magnetic field supports a fast alternation of the predominance of the capacitive and inductive effects.

The curves of figures 7, 8 and 9 show that the module of the thermal impedance is a decreasing function of the pulsation. The increase in the pulsation involves a reduction in the density of the minority carriers and consequently a reduction in the temperature. In this field, the capacitive effects appear there. Moreover, the application of the magnetic field increases the value of the module of the impedance. One can note that in the vicinity of resonances i.e. for frequencies lower or equal to resonances, the diffusion of the minority carriers is carried out in a considerable way and that has like corollary a light reduction in the impedance.

Diagram of Bode of the impedance for an illumination by the front face: phase of Z_{ph}

$$\varphi(x, \omega, B, m) = \arg(Z_{ph}(x, \omega, B, m))$$

$\varphi(x, \omega, B, m)$ Is the phase of the thermal Impedance

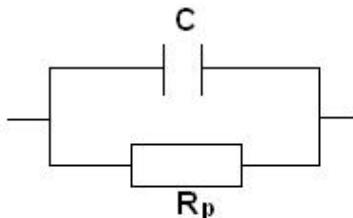


Fig.12 Circuitareequivalentofthe thermal impedance witho utmagneticfield applied

The diagram of figure 12 represents the equivalent electrical circuit which characterizes the effects observed starting from the diagrams of Bode (fig 7.8 and 9). C is the capacity and R_p parallel resistance

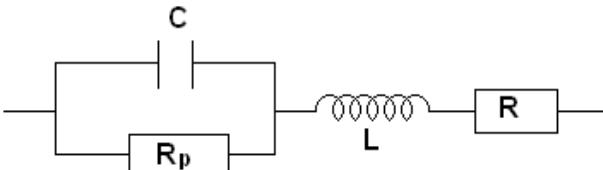


Fig.13: Circuitareequivalentofthe thermal impedance with magneticfield applied

The electrical circuit represented describes the two phenomena capacitive and inductive of the impedance (figure 10 and 11) where C is the capacity and R_p parallel resistance.

III. CONCLUSION

The resolution of the equation of continuity of the minority carrier in the base of the photovoltaic cell, allowed the study of certain phenomenological and electric parameters according to the frequency of modulation and the effect of the magnetic field. A degradation of the intrinsic properties of the photovoltaic cell, through these various parameters, was noted. Thanks to the use of phenomenological parameters like speed of recombination at the junction, the behavior of the photovoltaic cell can be studied through the density of carriers, the excess of temperature compared to the temperature of balance of material and the density flux of heat. The diagrams of Bode of the thermal impedance made it possible to establish the equivalent circuit of the photovoltaic cell under multispectral illumination and the effect of the magnetic field.

NOMENCLATURE

B(Tesla) Intensity of the magnetic field ω (rad.s⁻¹)

D_n^* (cm².s⁻¹) Angular frequency

1) Coefficient of diffusion of the minority carriers in the base

$D^*(\text{cm}^2.\text{s}^{-1})$ Complex coefficient of diffusion

$\delta(\text{cm}^3)$ Density of the photominority carriers created in the base according to depth x and time t

$G(x,t)(\text{cm}^{-3}.\text{s}^{-1})$ Rate of generation according to depth x and time t

$g(x)(\text{cm}^{-3}.\text{s}^{-1})$ Rate of generation according to depth x

$H(\mu\text{m})$ Thickness of the base

L_n^* (cm) Diffusion length of the minority carriers in the base

(cm) Complex diffusion length of the minority carriers in the base according to the frequency ω and of the magnetic field $K(\lambda)$ Constant in the expression of the density of the carriers

λ_g the wavelength of cut of the semiconductor estimated at 1,12 μm

λ_0 the minimal wavelength of the source of light is equal to 0,3 μm

$\alpha(\lambda)(\text{cm}^{-1})$ Absorption coefficient to the wavelength λ
 $R(\lambda)$ Coefficient of reflection of material to the wavelength λ
 $T_0(\text{°C})$ initial temperature of the photovoltaic cell
 $\Delta T(\text{°C})$ temperature variation
 $Z(\text{°C/W})$ thermal impedance
 $\Phi(\lambda)(\text{cm}^{-2}/\text{s})$ Incidental flow
 $k(\text{W/cm}^2/\text{°C})$ thermal conductivity
 $\Phi(\text{W/cm}^2)$ is the density flux of heat
 $E_g(\text{eV})$ energy of gap of silicon

$\sigma(\omega)$ Thermal coefficient of diffusion process

$\rho(\text{g/dm}^3)$ Density of volume of silicon

$C(\text{J/g/°C})$ Specific heat of silicon

REFERENCES

- Barro,F.I.,E.Nanema,A.Wereme,F.Zougmore and G.Sissoko,2001.Recombination parameters measurement insilicon doublesidedsurfacefield solarcell.J.Des.Sci.,1(1):76-80.
- Barro,F.I.,E.Nanema,F.Zougmore,A.Wereme,A.Ndiaye and G.Sissoko,2003.Transientstudyof doublesidedsiliconsolarcellunderconstantwhite biaslight:Determinationofrecombination parameters.J.Des.Sci.,3(1):10-14.
- Dème,M.M.,S.Sarr,R.Sam,S.Gueye,M.L.Samb,F.I.Barro and G.Sissoko,2009.Influenceofgrainsize, therecombinationvelocityatgrainboundariesand theangleofincidenceoflightontheenlargementofthespacechargezoneofasolarcellmonofaciale.J.Sci.,9(2):17-27.
- Diallo,H.L.,A.S.Maiga,A.Wereme and G.Sissoko,2008.New approach of both junction and back surface recombination velocity esina 3D modeling study of a polycrystalline silicon solar cell.Eur op. Phys.J.Appl.Phys.,42:203-211.
- Dieng,A.,O.H.Lemrabott,A.S.Maiga,A.Diao and G.Sissoko,2007.Impedancespectroscopymethod appliedtoelectricalparametersdeterminationon bifacialsiliconsolarcellundermagneticfield.J.ofSci.,7(3):48-52.
- Dieng,A.,N.Thiam,A.Thiam,A.S.Maiga and G.Sissoko,2011. Magneticfieldeffectontheelectricalparametersofapoly crystallinesiliconsolarcell.Res.J.Appl.Sci.Eng.Techn.,3(7):602-611.Flohr,T.and R.Helbig,1989.Determinationofminoritycarrierlifetimeandsurfacerecombinationvelocitybyoptical-beam-inducedcurrentmeasurementsatdifferentlightwavelengths.J.Appl.Phys.,66(7):3060-3065.LeQuangNam,R.M.,J.Nijs,M.Ghannam and J.Coppey,1992.Spectralresponseofsolarcells of high efficiency multicrystalline silicon.J.Phys.III,2(7):1305-1316.
- Lemrabott,O.H.,I.Ly,A.S.Maiga,A.Wereme,F.I.Barro and G.Sissoko,2008.Bulk and surface recombination parameters measurement in silicon doublesidedsolarcellunderconstant monochromatic illumination.J.Sci.,8(1):44-50.
- Hollenhorst,J.N.and G.Hasnain,1995.Frequency dependent hole diffusion in InGaAs double heterostructures.Appl.Phys.Lett.,67(15):22032205.Ly,I.,I.Ze rbo,M.Wade,M.Ndiaye,A.Dieng,A.Diao,N.Thiam,A.Thiam, M.M.Dione,F.I.Barro,A.S.Maiga and G.Sissoko,2011.Bifacial silicon solar cell under frequency modulation and monochromatic illumination: Recombination velocities and associated equivalent electrical circuits.Proceedings of

the 26th European Photovoltaic Solar Energy Conference and Exhibition, Hamburg-Germany. Neugroschel, A., P.J. Chen, S.C. Pao and F.A. Lindholm, 1978. Proc. 13th Photovol. Sp. Conf. 70. Ndiaye, M., Z.N. Bako, I. Zerbo, A. Dieng, F.I. Barro and G. Sissoko, 2008. Determination of electrical parameters of a solar cell under monochromatic frequency modulation, using diagrams Bode and Nyquist. J. Sci., 8(3):5968. Ould Brahim, M.S., I. Diagne, S. Tamba, F. Niang and G. Sissoko, 2011. Characterization of the minimum effective layer of thermal insulation material two plaster from the method of thermal impedance. Res. J. Appl. Sci. Eng. Techn., 3(4):338-344. Ricaud, A., 1997. Solar cells. Polytechnic and university presses romandes. Madougou, 2004.